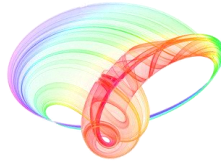


Book of abstracts



PHOTONICA2019

The Seventh International School and Conference on
Photonics, 26 August – 30 August 2019, Belgrade, Serbia

& Machine Learning with Photonics Symposium
(ML-Photonica 2019)



& ESUO Regional Workshop



& COST action CA16221



Editors: Milica Matijević, Marko Krstić and Petra Beličev

Belgrade, 2019

ABSTRACTS OF TUTORIAL, KEYNOTE, INVITED LECTURES,
PROGRESS REPORTS AND CONTRIBUTED PAPERS

of

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Optical and Structural Investigation of Cr₂O₃ Thin Films: the Effect of Thickness on Their Applicability in Differential Photodetectors

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We report an experimental study of Cr₂O₃ thin films (60, 300, 350 nm) deposited on silicon and glass substrates using the Balzers Sputtron II System. The structural and optical properties were investigated by means of AFM, XRD, UV-VIS, Raman and infrared spectroscopy, in order to determine the suitability of the as-obtained films as potential active layers in novel differential inorganic photodetectors. AFM measurements revealed that all films are well-deposited, without the presence of any cracks or voids. The crystalline peaks in the XRD spectra belonged to the trigonal Cr₂O₃ structure. UV-VIS measurements revealed a strong red shift in the absorption maxima with reducing film thickness. IR and Raman spectroscopy show a dependence of the characteristic vibrations on film thickness as well as on the substrate. In conclusion, our results indicate that the Cr₂O₃ film of 300 nm thickness is so far the most promising candidate as photoactive semiconducting layer in differential photodetectors.